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	Application No.	Applicant(s)	
Notice of Allowability	09/957,450	BULTMAN ET AL.	
	Examiner	Art Unit	
	Douglas N Washburn	2863	
	Lougias is syasilouiti	2003	
The MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS therewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIP of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this a or other appropriate communication IGHTS. This application is subject	pplication. If not included on will be mailed in due co	ourse. <b>THIS</b>
1. X This communication is responsive to paper filed 22 April 20	<u>004</u> .		
2. X The allowed claim(s) is/are <u>1793-1871 and 2057</u> .			
3. $igotimes$ The drawings filed on $20$ September $2001$ are accepted by	the Examiner.		
<ul> <li>4. ☐ Acknowledgment is made of a claim for foreign priority ur</li> <li>a) ☐ All b) ☐ Some* c) ☐ None of the:</li> <li>1. ☐ Certified copies of the priority documents have</li> </ul>			
2. Certified copies of the priority documents have	been received in Application No.	·	
3. Copies of the certified copies of the priority do	cuments have been received in this	s national stage application	on from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONN THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a repl IENT of this application.	y complying with the requ	irements
<ol> <li>A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give</li> </ol>	itted. Note the attached EXAMINE es reason(s) why the oath or declar	R'S AMENDMENT or NO ration is deficient.	TICE OF
6. CORRECTED DRAWINGS ( as "replacement sheets") mus	st be submitted.		
(a) ☐ including changes required by the Notice of Draftspers	son's Patent Drawing Review (PTC	0-948) attached	
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date	,		
(b) including changes required by the attached Examiner' Paper No./Mail Date	s Amendment / Comment or in the	Office action of	
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the draw he header according to 37 CFR 1.12	vings in the front (not the b 1(d).	pack) of
<ol> <li>DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT</li> </ol>	SIT OF BIOLOGICAL MATERIAL FOR THE DEPOSIT OF BIOLOGI	. must be submitted. No CAL MATERIAL.	ote the
Attachment(s)		D	450)
1. ☑ Notice of References Cited (PTO-892)		Patent Application (PTO-	-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summai Paper No./Mail D	)ate	
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date</li> </ol>			
4. Examiner's Comment Regarding Requirement for Deposit		ment of Reasons for Allow	vance
of Biological Material	9.		
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## **DETAILED ACTION**

1 Applicant canceled claims 1-1792, 1872-2056 and 2058-6632.

### Election/Restrictions

2 Applicant's election without traverse of claims 1793-1871 and 2057 in Paper No. 04/22/2004 is acknowledged.

#### Prior Art Cited

3 Sandland et al. (US 4,618,938) teaches an automatic semiconductor wafer inspection system which includes a wafer inspector, a system computer performing movement and function control and data storage functions and a high speed image computer. Patterned wafers selected for inspection are transported to a vacuum chuck located on an X-Y stage and positioned in a macro inspection station. Surface illumination is changed to test for macro defects. Reflected light is applied to a camera where the optical image is converted to an electrical representation, stored, and then processed by the high speed image computer. After a wafer has been positioned and inspected in the macro inspection station, it is moved to the micro inspection station. An autofocus arrangment focuses the objective lens to accomplish micro inspection tests. Sandland is silent regarding determining a first property and a second property of the specimen from one or more output signals during use. Sandland also fails to teach a remote computer configured to receive one or more output signals to determine a first property and a second property of the specimen.

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Sekine (US 5,912,732) teaches a surface inspection apparatus comprising a light source, a scan optical system, a moving unit, a light receiving unit, and a signal processing unit performing surface inspection based on signals from the light receiving unit. Sekine is silent in regard to determing a first property and a second property of a specimen from one or more output signals during use, wherein the first property comprises a presence of macro defects and the second property comprises a presence of micro defects. Sekine further is silent in regard to a remote computer configured to receive one or more output signals to determine a first property and a second property of a specimen from one or more output signals during use.

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Stern et al. (US 6,603,874) teaches a system and method for simultaneously obtaining a plurality of images of an object or pattern from a plurality of different viewpoints. A light source is positioned to illuminate at least a portion of an object. A plurality of light guides are positioned to simultaneously receive light reflected from the object and transmit the received light to a plurality of photodetectors. Signals generated by the photodetectors are processed and a plurality of images of the object are formed. Stern is silent regarding a remote computer configured to receive one or more output signals to determine a first property and a second property of a specimen from one or more output signals during use. Further, Stern is silent in regard to a first property comprising a presence of macro defects, and a second property comprising a presence of micro defects.

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Tanaka (US 6,629,051) teaches a defect inspection data processing system. The system includes a client computer having an image pickup section and a data transfer section. A database stores image data transferred from the client computer. The system also includes a host computer having a defect extraction section for extracting defect information from the image data stored in the database, and a judgment section for judging whether or not the inspected object is good, on the basis of the defect information extracted by the defect extraction section. Tanaka is silent in regard to determing a first property and a second property of a specimen from one or more output signals during use, wherein the first property comprises a presence of macro defects and the second property comprises a presence of micro defects.

Singh et al. (US 6,650,422) teaches a method and system for non-destructively detecting asymmetry in the profile of a feature formed on a wafer during the process of semiconductor fabrication. A beam of light or radiation is directed towards a feature and a reflected beam is detected. Data associated with the reflected beam is correlated with data associated with known feature profiles. Using the profile characteristics, an asymmetry of the feature is determined which is then used to generate feedback or feedforward process control data to compensate for or correct such asymmetry in subsequent processing. Singh is silent regarding a remote computer configured to receive one or more output signals to determine a first property and a second property of a specimen from one or more output signals during use. Further, Stern is silent in regard to a first property comprising a presence of macro defects, and a second property comprising a presence of micro defects.

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# Allowable Subject Matter

The following is an examiner's statement of reasons for allowance:

Claim 1793 recites, in part, "a processor coupled to the measurement device and configured to determine a first property and a second property of the specimen from the one or more output signals during use, wherein the first property comprises a presence of macro defects on the specimen, and wherein the second property comprises a presence of micro defects on the specimen". This feature in combination with the remaining claimed structure avoids the prior art of record.

Claims 1794-1871 depend from claim 1793.

Claim 2057 recites, in part, "the remote controller computer is configured to receive the at least partially processed one or more output signals and to determine a first property and a second property of the specimen from the at least partially processed one or more output signals during use, wherein the first property comprises a presence of macro defects on the specimen, and wherein the second property comprises a presence of micro defects on the specimen". This feature in combination with the remaining claimed structure avoids the prior art of record.

It is these limitations, which are not found, taught or suggested in the prior art of record, and are recited in the claimed combination that makes these claims allowable over the prior art.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Douglas N Washburn whose telephone number is (571) 272-2284. The examiner can normally be reached on Monday through Thursday 6:30 AM - 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John E Barlow can be reached on (571) 272-2269. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR.

Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

DNW

Supervisory Patr/it Examiner

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